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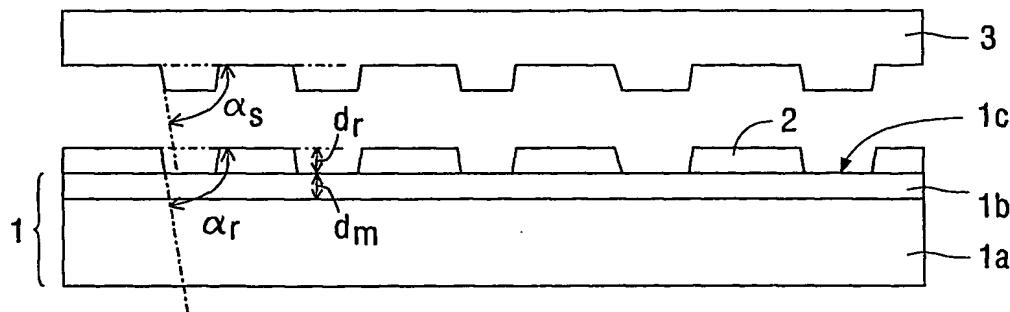
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(54) Title: PHOTOLITHOGRAPHIC PROCESS, STAMPER, USE OF SAID STAMPER AND OPTICAL DATA STORAGE MEDIUM



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(57) Abstract: A photolithographic process is described. It comprises the steps of: applying a photoresist layer (2) on a substrate (1), locally exposing the photoresist layer (2) to a radiation source with a suitable wavelength, providing a suitable liquid developer composition on the substrate (1), dissolving an exposed or unexposed region of the photoresist layer (2) with the developer composition, rinsing and drying the photoresist layer (2) thereby interrupting said dissolving step. The substrate (1) has a metallic surface (1c) in contact with the photoresist layer (2) and the photoresist layer (2) has a thickness $dr < 100\text{nm}$. A relatively high photoresist wall steepness is achieved of 70 degrees or more. The process may be used for the production of high density optical data storage media by using a stamper (3) produced with said process.



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